

**AMENDMENTS TO THE CLAIMS**

Please amend claim 18, as follows:

1 1. (Original) A tension mask for a color cathode-ray tube, comprising:  
2 a plurality of parallel strips separated by a predetermined distance from each other;  
3 a plurality of real bridges intersecting adjacent strips among said plurality of parallel strips  
4 to define slots, the slots accommodating electron beams to pass through; and  
5 a plurality of dummy bridges located in the slots, partially extending between but not  
6 intersecting the adjacent strips, said plurality of dummy bridges having projections facing each other  
7 without touching, said dummy bridges having an etching boundary located below the middle of said  
8 strips.

1 2. (Original) The tension mask of claim 1, with said plurality of real bridges being recessed  
2 by a predetermined depth from the top surface of said real bridges, and the thickness of each of said  
3 real bridges being smaller at the center than at the periphery of said real bridges.

1 3. (Original) The tension mask of claim 2, with the thickness of each of one said real bridges  
2 at the recessed center of the real bridges being approximately the same as the distance from the  
3 bottom of the strips to said etching boundaries of said dummy bridges.

1 4. (Original) The tension mask of claim 1, with each of said plurality of real bridges having  
2 a planar top surface.

1 5. (Original) The tension mask of claim 4, with the top or bottom surface of said real bridges  
2 being at the same level as the surfaces of said adjacent strips.

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1 6. (Original) The tension mask of claim 1, with the distance from the bottom of said strips  
2 to the etching boundaries of said dummy bridges being 0.25 times smaller than the thickness of said  
3 strips.

1 7. (Original) The tension mask of claim 6, with the thickness of each of said real bridges at  
2 the recessed center of said real bridges being approximately the same as the distance from the bottom  
3 of said strips to the etching boundaries of said dummy bridges.

1 8. (Original) The tension mask of claim 1, with the distance from the top of the strips to the  
2 etching boundaries of said dummy bridges being larger than the distance from the bottom of the  
3 strips to the etching boundaries of said dummy bridges, the top of the strips being on the electron  
4 beam emitting side and the bottom of the strips being on the electron beam entering side.

1 9. (Original) The tension mask of claim 1, with the relative position of each of the slots at  
2 the beam entering side with respect to the beam emitting side of said tension mask being shifted

3 toward the center of said tension mask as the locations of the slots become closer to the periphery  
4 of said tension mask.

1 10. (Original) The tension mask of claim 9, with the relative position of each of the slots at  
2 the beam entering side being shifted toward the center of said tension mask by etching a portion of  
3 each slot on the beam emitting side with a predetermined width, and shifting an etch of a portion  
4 of each slot on the beam emitting side with a predetermined width towards the center of said tension  
5 mask with respect to the etch of the portion of the slot on the beam emitting side, the etch on the  
6 beam emitting side and the etch on the beam entering side forming one of the slots of said tension  
7 mask.

1 11. (Original) The tension mask of claim 9, with the center of said tension mask being a  
2 center line accross a width of said tension mask.

1 12. (Original) The tension mask of claim 1, with the relative position of the gap between the  
2 facing dummy bridges being shifted toward the center or the periphery of said tension mask as the  
3 locations of said dummy bridges become closer to the periphery of said tension mask.

1 13. (Original) The tension mask of claim 12, with the relative position of the gap between  
2 the facing dummy bridges being shifted toward the center or the periphery of said tension mask  
3 according to the reduction of the clipping of the electron beams.

1 14. (Original) The tension mask of claim 1, with the width of each of said dummy bridges  
2 along said strips becoming narrow as the locations of said dummy bridges come closer to the  
3 periphery of said tension mask. /

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1 15. (Original) The tension mask of claim 12, with the width of each of said dummy bridges  
2 along said strips becoming narrow as the locations of said dummy bridges come closer to the  
3 periphery of said tension mask.

1 16. (Original) The tension mask of claim 1, with the area of each of the dummy bridges  
2 becoming smaller as the locations of the dummy bridges come closer to the periphery of the tension  
3 mask.

1 17. (Original) The tension mask of claim 1, with said adjacent strips having rounded portions  
2 to reduce the clipping of electron beams.

1 18. (Currently Amended) The tension mask of claim 1, with the width of each of the slots  
2 at the electron beam ~~entering~~ emitting side being wider than at the electron beam entering side.

1 19. (Original) The tension mask of claim 1, being manufactured by an exposure mask  
2 comprising a pair of upper and lower exposure masks to be aligned over the top and bottom surfaces

3 of a steel foil, respectively, to accommodate exposure of photosensitive layers deposited on said steel  
4 foil, said upper exposure mask having a pattern including a series of parallel upper light transmission  
5 portions arranged in lines, said lower exposure mask comprising:

6 a pattern including a series of parallel lower light transmission portions arranged in lines;

7 a plurality of first light shielding portions intersecting adjacent lower light transmission  
portions among said series of parallel lower light transmission portions; and

8 a plurality of second light shielding portions partially extending between the adjacent lower  
9 light transmission portions.  
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1 20. (Original) A tension mask for a color cathode-ray tube, comprising:

2 a plurality of parallel strips separated by a predetermined distance from each other;

3 a plurality of real bridges intersecting adjacent strips among said plurality of parallel strips  
4 to define slots accommodating electron beams to pass through;

5 a plurality of dummy bridges located in the slots, partially extending between but not  
6 intersecting the adjacent strips, said dummy bridges facing each other, an etching boundary of each  
7 of said dummy bridges being located below the middle of said strips;

8 a pair of first rounded portions formed with a first thickness at the beam emitting side of each  
9 of the slots, partially extending from the adjacent strips; and

10 a pair of second rounded portions formed with a second width at the beam entering side of  
11 each of the slots, partially extending from the adjacent strips.

1           21. (Original) The tension mask of claim 20, with the relative position of each of the slots  
2           at the beam entering side with respect to the beam emitting side being shifted toward the center of  
3           the tension mask as the locations of the slots come closer to the periphery of the tension mask.

1           22. (Original) The tension mask of claim 20, with the relative position of the gap between  
2           the facing dummy bridges being shifted toward the center or the periphery of said tension mask as  
3           the locations of said dummy bridges come closer to the periphery of said tension mask.

1           23. (Original) The tension mask of claim 20, with said plurality of real bridges being recessed  
2           by a predetermined depth from the top surface of said real bridges, and the thickness of each of said  
3           real bridges being smaller at the center than at the periphery of said real bridges.

1           24. (Original) The tension mask of claim 20, with each of said plurality of real bridges having  
2           a planar top surface.

1           25. (Withdrawn) A method for manufacturing a tension mask for a color cathode-ray tube,  
2           comprising:

3           depositing photosensitive layers over the top and bottom surfaces of a foil;  
4           aligning an upper exposure mask with a pattern including a plurality of parallel upper light  
5           transmission portions arranged in lines over the top surface of said foil;  
6           aligning a lower exposure mask with a pattern over the bottom surface of said foil, the pattern

7 of said lower exposure mask including a plurality of parallel lower light transmission portions  
8 arranged in lines, a plurality of first light shielding portions intersecting adjacent lower light  
9 transmission portions among said plurality of parallel lower light transmission portions, and a  
10 plurality of second light shielding portions partially extending between the edges of the adjacent  
11 lower light transmission portions;

12 exposing said photosensitive layers uncovered with the lower and upper exposure masks  
13 using an exposure light source;

14 removing said upper and lower exposure masks from said foil and developing the  
15 photosensitive layers remaining on said foil; and

16 etching said foil having undergone the developing process.

1 26. (Withdrawn) The method of claim 25, with said foil being of a steel material.

1 27. (Withdrawn) The method of claim 26, with the width of each of said upper light  
2 transmission portion being two or more times larger than the width of each of the lower light  
3 transmission portion.

1 28. (Withdrawn) The method of claim 26, with the pattern of said upper exposure mask  
2 further comprising a plurality of light shielding portions intersecting the adjacent upper transmission  
3 portions, corresponding to said first light shielding portions of said lower exposure mask.

1           29. (Withdrawn) The method of claim 28, with the width of each of said light shielding  
2 portions of said upper exposure mask being smaller than the width of each of said first light shielding  
3 portions of said lower exposure mask.

1           30. (Withdrawn) An exposure mask for use in the manufacture of a tension mask for a color  
2 cathode-ray tube, comprising a pair of upper and lower exposure masks to be aligned over the top  
3 and bottom surfaces of a steel foil, respectively, to accommodate exposure of photosensitive layers  
4 deposited on said steel foil, said upper exposure mask having a pattern including a series of parallel  
5 upper light transmission portions arranged in lines, said lower exposure mask comprising:

6           a pattern including a series of parallel lower light transmission portions arranged in lines;

7           a plurality of first light shielding portions intersecting adjacent lower light transmission  
8 portions among said series of parallel lower light transmission portions; and

9           a plurality of second light shielding portions partially extending between the adjacent lower  
10 light transmission portions.

1           31. (Withdrawn) The exposure mask of claim 30, with the width of each of said upper light  
2 transmission portion being two or more times larger than the width of each of said lower light  
3 transmission portion.

1           32. (Withdrawn) The exposure mask of claim 30, with the pattern of said upper exposure  
2 mask further comprising a plurality of light shielding portions intersecting the adjacent upper



3 transmission portions, corresponding to said first light shielding portions of said lower exposure mask.

*Amended*  
*A<sup>1</sup>*  
2 33. (Withdrawn) The exposure mask of claim 32, with the width of each of said light  
3 shielding portions of the upper exposure mask being smaller than the width of each of said first light  
shielding portions of said lower exposure mask.

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